



<b>[FA1] Sputtering / Ion Beam Applications</b>	
<b>Date / Time</b>	July 27 (Fri.), 2018 / 09:00-10:20
<b>Place</b>	Room A (#104~106)
<b>Session Chair(s)</b>	Andreas Pflug (Fraunhofer Inst. for Surface Engineering and Thin Films IST, Germany) Jun Xu (Dalian Univ. of Tech., China)

**FA1-1** **09:00-09:20**

**Effect of Deposition Temperature on the Ferroelectric Properties of Y-Doped HfO<sub>2</sub> Thin Film Prepared by Medium-Frequency Reactive Magnetron Co-Sputtering**

Yu Zhang<sup>1</sup>, Jun Xu<sup>1</sup>, Da-Yu Zhou<sup>1</sup>, Hang-Hang Wang<sup>1</sup>, Wen-Qi Lu<sup>1</sup>, Chi-Kyu Choi<sup>2</sup>, Jeong-Yong Lee<sup>3</sup>, and Sung-Kyu Kim<sup>3</sup>

<sup>1</sup>Dalian Univ. of Tech., China, <sup>2</sup>Jeju Nat'l Univ., Korea, <sup>3</sup>KAIST, Korea

**FA1-2** **09:20-09:40**

**EXAFS Study of Zinc Ferrite Thin Film on Glass Substrate**

Jitendra Pal Singh and Keun Hwa Chae

*KIST, Korea*

**FA1-3** **09:40-10:00**

**Magnetron Sputtering System Design for TSV(through silicon via) Applications**

Junghoon Joo

*Kunsan Nat'l Univ., Korea*

**FA1-4** **10:00-10:20**

**Damage Control for Transistor Junction Engineering by Using Aromatic Hydrocarbon Ion Implantation**

Kyungwon Lee<sup>1</sup>, DaeHo Yoon<sup>1</sup>, Dwight Roh<sup>2</sup>, Michael Ameen<sup>2</sup>, Ronald Reece<sup>2</sup>, and Rimpyo Hong<sup>2</sup>

<sup>1</sup>Sungkyunkwan Univ., Korea, <sup>2</sup>Axcelis Technologies, Inc., USA